



Silent Forum – Meet the Technology Experts

A new exhibition experience

The Silent Forum is a new feature of PSE2026, bringing innovation directly to the exhibition floor. In short presentations, exhibitors introduce new technologies, products and industrial solutions while sharing current developments from their companies. Discover practical innovations, gain fresh inspiration and connect with experts in a relaxed exhibition atmosphere.

PROGRAM

Tuesday, September 1, 2026 | Foyer Hall 1

Silent Forum I

Artificial Intelligence, Modelling & Simulation –

Digital Solutions for Coating Industry

01.09.2026 | 10:30 – 12:00 | Foyer Hall 1

Application of an open-source plasma simulation tool in industrial deposition and etching processes

Asim Mirza, boltzplatz - numerical plasma dynamics GmbH, Germany

Idea - simulation - test: a new way of operational mode development for bipolar plasma generators

Tim Gehring, TRUMPF Hüttinger GmbH + Co. KG, Freiburg, Baden-Württemberg, Germany

Multiphysics Simulation and AI Models for Plasma Coating Applications

Annette Pahl, Comsol Multiphysics GmbH, Germany

Silent Forum II

„Plasma & Process Analytics“

01.09.2026 | 13:30 – 15:00 | Foyer Hall 1

Moderation: Anas Ghailane, AVALUXE International GmbH, Germany

The EMICON System - Cutting-Edge Plasma Monitoring and Process Control for Development, Production and Machine Learning (ML)

Thomas Schütte, PLASUS GmbH, Germany

Multipole Resonance Probe Revisited: Advanced Capabilities for Modern Plasma Processes

Moritz Oberberg, House of Plasma GmbH, Germany

Aurion: Plasma, Radio Frequency, and More

Michael Schneider, Aurion Anlagentechnik GmbH, Germany



PROGRAM

Wednesday, September 2, 2026 | 09:00 – 16:00 | Foyer Hall 1

Silent Forum III

„Coatings and Equipment for Energy Technologies“

02.09.2026 | 10:30 – 12:00 | Foyer Hall 1

Moderation: André Wahl, Energy Saxony, Germany

From Batteries to Fusion: Vacuum-Based Plasma and Electron Beam Technologies for Energy Applications

Christian May, Fraunhofer Institute for Electron Beam and Plasma Technology FEP, Germany

Graphite doped Lithium based sputtering targets for DC deposition of LIPON for thin film batteries applications

Peter Polcik, Plansee Composite Materials GmbH

TBA

André Hieke, Ionbond, The Netherlands

Silent Forum IV

„Atomic Layer Deposition“

02.09.2026 | 13:30 – 15:00 | Foyer Hall 1

Moderation: Martin Knaut, IHM, Technical University Dresden, Germany

ALD4EMO – ALD for Energy Technologies

Katrin Ferse, EFDS e.V., Germany

Integrated Fast Atomic Layer Processing (FALP):

Combined ALE and Ion-Enhanced PEALD Enabling Polycrystalline Growth and CD

Control for Double Patterning on a Thermally-Coupled 300 mm ESC

Stephan Wege, Plasway-Technologies GmbH, Germany

TBA-ALD

Jessica Schneidewind, SENTECH Instruments GmbH, Germany

In-situ Monitoring of Atomic Layer Processes

Martin Knaut, ALS Metrology GmbH, Germany

Productive automation for ALD-processes inside and outside vacuum

Aron Strobel, LSA GmbH, Germany

This Program is organized by the EFDS in cooperation with the Network ALD4EMO – Atomic Layer Deposition for Energy, Medicine and Optics as well as the networks PLASMA GERMANY and Energy Saxony. Industrial Experts from Energy Technologies are invited to join the organized “Energy Delegation” and visit special events and exhibiting companies in a guided tour.